

## PHYS-E0421 Solid-State Physics (5cr), Spring 2019

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Lecture 7, 1/4/2019













- When is large void/inclusion 3D defect and when is it surface/interface (2D)?
- Compare surface atom to an atom next to single vacancy…



- E.g. iron can be either bcc or fcc, depending on temperature. Thus one could expect that the related energy cost is small.
- Twin boundary: domains with reflection
- Inversion domain boundary: domains with inversion. Need to have a material without inversion symmetry.
- Anti-phase boundary: connecting domains with atoms in opposite order e.g. Ga/N -> N/Ga. Necessarily leads to homopolar bonds (N-N or Ga-Ga)











- Hexagonal shape further away, due to minizing edge energy (maximizing the most stable edges). Or, alternatively, the most reactive (i.e., unstable) edges/sites grow the fastest, since the adsorbtion energy is highest.



- Dislocations cannot be healed locally. Need to heal the lattice from dislocation all the way to the edge, or glide the dislocation to the edge.



- Force/area = energy/volume



- Force is derivative of energy => sigma = 1/A\*dU/dx

## **Plastic deformation**





- Elastic limit (yield strength) depends on dislocation density. Usually, small grains have smaller density. Moreover, dislocations can not easily move from one grain to another. Thus polycrystalline has higher elastic limit.
- Dislocation motion can also be affected by alloying and introducing impurities/precipitates



- Antisite in compounds, e.g. Ga in As site of GaAs lattice.



- E(N) is the total (binding) energy of the system with N atoms
- Connection to cohesive/atomization energy E(coh)
- With covalent materials, if each atom has four bonds  $E(bond) = E(coh)/4$ . Then, very approximately, Ef=E(bond)\*#(broken bonds)=E(coh). In Si, E(coh)=4.6, Ef=3.6. Difference arising from relaxation of atom positions and rebonding.



 $- U = n^*Ff$ 





- exp(2.4)=11, but (here) temperature independent



- N is the number of atoms in the material. ln(n) has very slow dependence on n.
- Can only form if N is very small, or e.g the material is very thin, say, graphene, whereby 1D defects become point defects.



- Fig 3.5a is wrong in Elliott



- Na can not localize the electron next to it on the surface, but it can be localized on the vacancy, surrounded by positive ions





- NaCl irradiated with x-rays



- E.g. ruby absorbs yellow-green light, thus appears as red.



- Due to interaction of electrons in the defect, it's not possible to have Si vacancy with charge state +4 or -4, or even +-3



- ODC: e.g. in CuInSe2, the formation energy of Cu vacancy (-1 charge) and In  $@Cu$  antisite (+2 charge) are so low that their concentration can be  $~10\%$ . Due to Coulomb interaction, the defects are ordered similar to ionic crystals.









- Direct exchange tends to be quite rare as it requires lot of space



- Classical treatment should probably yield same result: i.e., consider particles with MB velocity distribution and see how many have sufficient kinetic energy to overcome the barrier.
- Potential energy landscape, but no dynamical effects. In reality, the hop might be possible in principle, but require that the positions and velocities of all particles are just right, and thus the prefactor would be very low.
- v0 typically  $\sim$  1e12 1/s
- Activation energy = defect formation energy + migration barrier. Relevant if defects are (spontaneously) generated before migrating.





- C in Fe at RT:  $D=10e-20 \Rightarrow L=sqrt(Dt)=1 \text{ Å}$  in 1s, 10 mum/s in 700C, surface hardening of iron.
- H in V at RT: D=1e-4 => L=0.1mm in 1s. It's difficult to contain hydrogen with metal tanks (I guess carbon fiber something is usually used).







- If time allows





- Defects in amorphous material: dangling bonds, wrong bonds (e.g. Si-Si). No dislocations, stacking faults, etc. How about vacancies/interstitials?
- In quasicrystals, the same as in periodic lattices. Dislocations, stacking faults possible (?)

